

Supporting Information

Direct fabrication of 3D silica-like microstructures from epoxy-functionalized polyhedral oligomeric silsesquioxane (POSS)

Jun Hyuk Moon,^{‡a} Jin Seok Seo,^{‡b} Yongan Xu^b and Shu Yang^{*b}

^a Department of Chemical and Biomolecular Engineering, Sogang University, 1 Shinsu-dong, Mapo-gu, Seoul (Korea)

^b Materials Science and Engineering, University of Pennsylvania, PA, 19104 (USA)

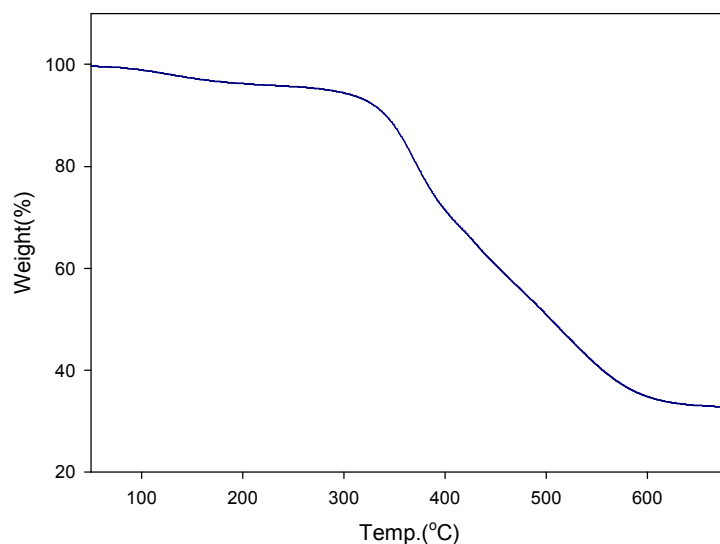


Figure S1. Thermogravimetric analysis of epoxy-POSS photoresist in air environment. The relative volume was measured by increasing the temperature up to 700 °C at a heating rate of 10 °C/min.